



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:)	
)	ATTORNEY FILE NO.:
Inventors: Joshi et al.)	SLA0786
)	
Serial No.: 10/812,591)	
)	Examiner: Sarkar, Asok
)	
Filed: March 29, 2004)	Customer No.: 55,286
)	
Title: HIGH DENSITY PLASMA)	Group Art: 2891
PROCESS FOR THE)	
FORMATION OF SILICON)	Confirmation No.: 2314
DIOXIDE ON SILICON)	
CARBIDE SUBSTRATES)	

Mail Stop Issue Fee
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

ISSUE FEE RESPONSE

This paper is responsive to a Notice of Allowance mailed on
June 8, 2006. Enclosed are:

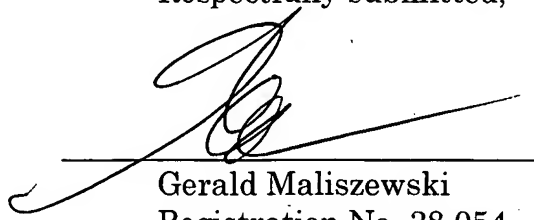
two copies of the Issue Fee Transmittal form;
6 sheets of Replacement drawings; and,
a PTO-2038 form, in the amount of \$1709.

REMARKS

The Applicant neither expressly agrees nor disagrees with the stated reasons for the allowance of the claims.

Respectfully submitted,

Date: 6/17/2006


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